

92 13. (Amended) An illumination system including a two-dimensional phase type element manufactured in accordance with a method as recited in [any one of Claims 2-12] Claim 2 or 3. X

14 15. (Amended) A device manufacturing method[,]  
comprising the steps of:

93 exposing a wafer to a device pattern[, by use of]  
using a projection exposure apparatus as recited in Claim <sup>13</sup>~~14~~; X

and

developing the exposed wafer.

Remarks

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The claims are 1-15, with claims 1-3 being independent. Claims 2-4, 6-13 and 15 have been amended to better define the invention. In particular, claims 8-13 have been amended to remove improper multiple dependency. Claims 2-4, 6, 7 and 15 have been amended as to formal matters. Consideration of the claims is respectfully requested.

Applicant's undersigned attorney may be reached in our New York office by telephone at (212) 218-2100. All

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Respectfully submitted,

  
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